Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"6375756".pn. or "6593548".pn.	US-PGPUB; USPAT	OR	ON	2004/12/27 11:45
L2	1	"5849092".PN.	USPAT; USOCR	OR	ON	2004/12/27 11:48
L3	1	"5926743".PN.	USPAT; USOCR	OR	ON	2004/12/27 11:49
L4	1	"6143128".PN.	USPAT; USOCR	OR	ON	2004/12/27 11:50
L5	1	"6201219".PN.	USPAT; USOCR	OR	ON	2004/12/27 11:51
L6	1	"6242347".PN.	USPAT; USOCR	OR	ON	2004/12/27 11:51
L7	1	"6255222".PN.	USPAT; USOCR	OR	ON	2004/12/27 11:51
L8	5	(Ishibashi.in. or Anelva.as. or (Japan near2 Science).as.) and ((Pt or platinum) near3 (filament or coil or mesh or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 11:54
L9	5	(Ishibashi.in. or Anelva.as. or (Japan near2 Science).as.) and ((Pt or platinum) near3 (filament or coil or mesh or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 11:54
L11	18	(Ishibashi.in. or Anelva.as. or (Japan near2 Science).as.) and ((Pt or platinum) with (clean$3 or etch$3 or ash$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 11:55
L12	18	(Ishibashi.in. or Anelva.as. or (Japan near2 Science).as.) and ((Pt or platinum) with (clean$3 or etch$3 or ash$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 11:56
L13	8	(Ishibashi.in. or Anelva.as. or (Japan near2 Science).as.) and ((Pt or platinum) with (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 11:59
L14	4	L13 not L9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 11:59

L16	19	(Ishibashi.in. or Anelva.as. or (Japan near2 Science).as.) and (((clean$3 or etch$3 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or F2 or "F.sub.2" or Cl2 or "Cl.sub.2" or $8fluoride or $8chloride or $8chlorine or $8fluorine) near2 gas) same (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:02
L17	2492	(427/561,562,569,585,570,573).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L18	850	(427/235,237).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L19	2707	(427/248.1,255.23,255.28).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L20	536	(427/444).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L21	905	(118/722,70).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L22	2224	(134/1.1,1.2,1.3,19).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L23	509	(216/37,63).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:04
L24	72	(118/723HC).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L25	2492	(427/561,562,569,585,570,573).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L26	850	(427/235,237).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L27	2707	(427/248.1,255.23,255.28).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L28	536	(427/444).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L29	905	(118/722,70).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05

L30	2224	(134/1.1,1.2,1.3,19).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L31	509	(216/37,63).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L32	72	(118/723HC).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/27 12:05
L33	8693	L25 L26 L27 L28 L29 L30 L31 L32	US-PGPUB; USPAT	OR	ON	2004/12/27 12:05
L34	0	L32 and L31	US-PGPUB; USPAT	OR	ON	2004/12/27 12:05
L35	43	L30 and (L31 or L32)	US-PGPUB; USPAT	OR	ON	2004/12/27 12:05
L36	5	L32 and (Pt or platinum)	US-PGPUB; USPAT	OR	ON	2004/12/27 12:06
L37	51	L31 and (Pt or platinum)	US-PGPUB; USPAT	OR	ON	2004/12/27 12:06
L38	8693	L25 L26 L27 L28 L29 L30 L31 L32	US-PGPUB; USPAT	OR	ON	2004/12/27 12:07
L39	13	L38 and ((Pt or platinum) near5 (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT	OR	ON	2004/12/27 12:07
L41	15	L38 and ((Pt or platinum) near8 (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT	OR	ON	2004/12/27 12:09
L42	77	L38 and ((Pt or platinum) with (clean$3 or etch$3))	US-PGPUB; USPAT	OR	ON	2004/12/27 12:10
L44	53	L38 and (((clean$3 or etch$3 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide) near2 gas) with (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT	OR	ON	2004/12/27 12:11
L45	4102	((Pt or platinum) with (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT	OR	ON	2004/12/27 12:13
L46	4102	((Pt or platinum) with (filament or coil or ((heat$3 or hot) near2 element)))	US-PGPUB; USPAT	OR	ON	2004/12/27 12:13

L47	111	L46 same (((clean$3 or etch$3 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide) near2 gas) or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:14
L48	27	L46 same (clean$3 or etch$3) same (fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:15
L49	1164	(Pt or platinum) same ((clean$3 or etch$3) with (fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:16
L50	1164	(Pt or platinum) same ((clean$3 or etch$3) with (fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:17
L51	20	L50 and L38	US-PGPUB; USPAT	OR	ON	2004/12/27 12:17

L52	235	((Pt or platinum) same (coil or wire or filament or ((heat$3 or hot) adj element) or mesh)) and ((clean$3 or etch$3) with (wall or chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") near3 (clean$3 or etch$3 or gas$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:22
L53	15	L52 and L33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:21
L54	235	((Pt or platinum) same (coil or wire or filament or ((heat$3 or hot) adj element) or mesh)) and ((clean$3 or etch$3) with (wall or chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") near3 (clean$3 or etch$3 or gas$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:29
L55	15	L54 and L33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:24
L56	220	L54 not L55	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:24

L57	670	((coil or wire or filament or ((heat$3 or hot) adj element) or mesh) near5 (heat$4 or hot or activat$6 or ioniz$6)) and ((clean$3 or etch$3 or remov$6) with (wall) with (chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") with (clean$3 or etch$3 or gas$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:39
L58	109	L57 and L33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:33
L59	901	((coil or wire or filament or element or mesh) near5 (heat$4 or hot or activat$6 or ioniz$6)) and ((clean$3 or etch$3 or remov$6) with (wall) with (chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") with (clean$3 or etch$3 or gas$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:42
L60	188	L59 and (Pt or platinum)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:41

L61	527	((coil or wire or filament or element or mesh) with (heat$4 or hot or activat$6 or ioniz$6 or dissociat$5 or disassociat$5) with (gas$3 or clean$4 or etch$4 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6")) and ((clean$3 or etch$3 or remov$6) with (wall) with (chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") with (clean$3 or etch$3 or gas$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 13:01
L62	1	"5879574".pn. and (coil or wire or filament)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:52
L63	18	L61 and ((coil or wire or filament or element or mesh) with (Pt or platinum))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:53
L64	72	L61 and L33	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 12:55

| L65 | 26 | ((coil or wire or filament or element or mesh) with (heat$4 or hot) with (activat$6 or ioniz$6 or dissociat$5 or disassociat$5) with (gas$3 or clean$4 or etch$4 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6")) and ((clean$3 or etch$3 or remov$6) with (wall) with (chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") with (clean$3 or etch$3 or gas$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/27 13:13 |
| L66 | 8 | L65 and (Pt or platinum) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/27 13:07 |

| L67 | 0 | ((Pt or platinum) with (heat$4 or hot) with (activat$6 or ioniz$6 or dissociat$5 or disassociat$5) with (gas$3 or clean$4 or etch$4 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6")) and ((clean$3 or etch$3 or remov$6) with (wall) with (chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") with (clean$3 or etch$3 or gas$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/27 13:08 |

L68	3	((Pt or platinum) same (coil or wire or filament or element or mesh) with (heat$4 or hot) with (activat$6 or ioniz$6 or dissociat$5 or disassociat$5) with (gas$3 or clean$4 or etch$4 or fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6")) and ((clean$3 or etch$3 or remov$6) with (wall or chamber or reactor or vessel or vessell)) and ((fluorine or chlorine or fluorin$5 or chlorin$5 or halogen$5 or halide or Cl2 or F2 or "Cl.sub.2" or "F.sub.2" or $8fluoride or $8chloride or NF3 or "NF.sub.3" or CF4 or "CF.sub.4" or C2F6 or "C.sub.2F.sub.6" or "C.sub.2 F.sub.6" or C3F8 or "C.sub.3 F.sub.8" or "C.sub.3F.sub.8" or CCl4 or "CCl.sub.4" or C2ClF5 or ClF3 or "ClF.sub.3" or CClF3 or "CClF.sub.3" or SF6 or "SF.sub.6") with (clean$3 or etch$3 or gas$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 13:20
L69	2	(MOS near2 sensor with etch$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 13:21
L70	386	(sensor with etch$4 with chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 13:21
L71	25	(sensor with etch$4 with (plac$4 or dispos$5 or locat$4) near3 chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 13:25
L72	2100	(substrate with etch$4 with sensor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/27 13:25

| L73 | 6 | L72 and L33 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2004/12/27 13:26 |